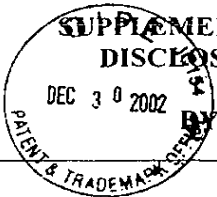


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				Applicant: Josephson et al.			
				Filed: July 11, 2001		Art Unit: 1725	
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